



## PATENT ABSTRACTS OF JAPAN

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(71) Applicant: FUJITSU LTD

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(72) Inventor: MATSUYAMA TAKAYOSHI

(54) METHOD FOR BONDING PELLICLE,  
PELLICLE AND MASK

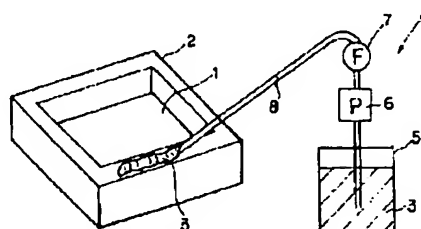
## (57) Abstract:

**PURPOSE:** To provide a pellicle which can easily be exfoliated from a mask without contaminating or damaging them and can enhance the yield of semiconductor devices.

**CONSTITUTION:** One side of the frame member 2 of a pellicle with a pellicle film 1 stuck to the other side is coated with an adhesive member 3 which is dissolved in a solvent and a mask is bonded to the pellicle with

the adhesive member 3 so that at least a face of the mask with a formed mask pattern is covered with the pellicle.

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Reference 1: Japanese Patent Application Laid Open No. S62-288842

Title of the Invention: Protective Dustproof Body for Photomask or Reticle

Filing Date: June 9, 1986

Applicant: Tosoh Corporation

Extract:

Claim describes a protective dustproof body for photomasks or reticles, which is a transparent thin cover made of synthetic quartz glass disposed at a constant distance from the surface of a substrate.